



NOEL Technologies

LPCVD PROCESS

Process	Thickness	Tolerance	Temperature Range
LPCVD Nitride	500A-3KA	±5%	750°C ±10%
Amorphous Silicon	200A-2KA	±5%	525°C ±10%
Undoped PolySilicon	200A-10KA	±5%	620°C ±10%

WIWNU: Wafer-within-Wafer Non-Uniformity: ±5% @ Range

Wafer Size

mm	Inches
50	2
100	4
125	5
150	6
200	8
300*	12

Note: 300mm-LPCVD Nitride only.Noel does not offer Amorphous Silicon-Undoped Poly on 300 mm.

Incoming Inspection of Wafers.
SRD, Spin Rinse Dry

Note:

- Upon inspection of wafers, additional cleaning may be required. Customer will be notified for disposition of material to receive the following:
 - SC1/SC2
 - Kiss Polish
- Additional processing and or cleaning may result in an additional charge.